



**P.E.S. College of Engineering, Mandya - 571 401**  
*(An Autonomous Institution affiliated to VTU, Belagavi)*  
**Fifth Semester, B.E. - Electronics and Communication Engineering**  
**Semester End Examination; Feb. - 2021**  
**Digital CMOS VLSI Design**

Time: 3 hrs

Max. Marks: 100

**Note: I) PART - A** is compulsory. Two marks for each question.**II) PART - B:** Answer any **Two** sub questions (from a, b, c) for Maximum of **18 marks** from each unit.

Q. No.	Questions	Marks
<b>I : PART - A</b>		<b>10</b>
I a.	With the linear and saturation condition for PMOS device, write the drain current expression.	2
b.	Give the critical voltages ( $V_{IL}$ and $V_{IH}$ ) expression for symmetric CMOS inverter.	2
c.	Implement the 2:1 multiplexer using transmission gates.	2
d.	Design a domino CMOS logic circuit for the Boolean function; $Z = \overline{AB + (C + D)(E + F) + GH}$	2
e.	List out any two causes for latch up problem in CMOS chips.	2
<b>II : PART - B</b>		<b>90</b>
<b>UNIT - I</b>		<b>18</b>
1 a.	Explain the formation of depletion region and inversion layer in an $n$ -channel enhancement type MOSFET with neat figure and band diagram.	9
b.	Analyse the oxide related capacitances of MOSFET with relevant equation.	9
c.	Calculate the threshold voltage $V_{TO}$ at $V_{SB} = 0$ , for a polysilicon gate $n$ -channel MOS transistor with the following parameters: Substrate doping density $N_A = 10^{16} \text{ cm}^{-3}$ , Polysilicon gate doping density $N_D = 2 \times 10^{20} \text{ cm}^{-3}$ , gate oxide thickness $t_{ox} = 500 \text{ \AA}$ , and oxide interface fixed charge density $N_{ox} = 4 \times 10^{10} \text{ cm}^{-2}$ . Assume; $\phi_F(\text{gate}) = 0.55 \text{ V}$ , $\epsilon_{ox} = 3.97 \epsilon_0$ , $\epsilon_{si} = 11.7 \epsilon_0$ and $n_i = 1.45 \times 10^{10} \text{ cm}^{-3}$	9
<b>UNIT - II</b>		<b>18</b>
2 a.	Draw the circuit diagram and VTC indicating critical voltage pointer for CMOS inverter. Analyze the circuit to calculate $V_{IL}$ and $V_{IH}$ .	9
b.	Discuss the calculation of interconnect delay of RC network.	9
c.	For depletion load NMOS inverter with $V_{DD} = 5 \text{ V}$ , $V_{TO, driver} = 1.0 \text{ V}$ , $V_{TO, load} = -3 \text{ V}$ , $(W/L)_{driver} = 2$ , $(W/L)_{load} = 1/3$ , $K'_{n driver} = K'_{n load} = 25 \mu\text{A/V}^2$ , $\gamma = 0.4 \text{ V}^{1/2}$ , $\phi_F = -0.3 \text{ V}$ , $V_{IH} = 2.43 \text{ V}$ . Calculate the Noise margin.	9

**UNIT - III****18**

- 3 a. Analyze the CMOS NOR2 gate with relative equation. 9
- b. Analyze the bias conditions and operating regions of CMOS transmission gates. 9
- c. With relevant diagram and equation, explain the behavior of Bistable elements. 9

**UNIT - IV****18**

- 4 a. Analyze the voltage bootstrapping with relevant equations. 9
- b. Analyze the charge storage and charge leakage phenomenon at a soft node in CMOS network. 9
- c. Analyze the basic principle of operation of NP Domino logic. 9

**UNIT - V****18**

- 5 a. Discuss the switching delay in BiCMOS logic circuit with related circuit diagram and waveform. 9
- b. Analyze the ESD protection system in CMOS circuit with relevant example. 9
- c. Discuss the process of on-chip clock generation and distribution in CMOS circuit. 9

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